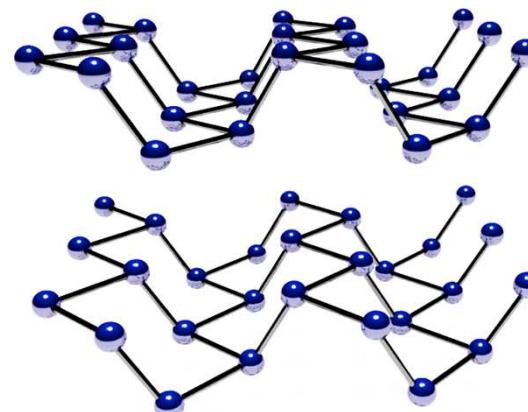


Black Phosphorus Field Effect Transistors: Passivation By Oxidation, and the Role of Anisotropy in Magnetotransport

Tomasz Szkopek



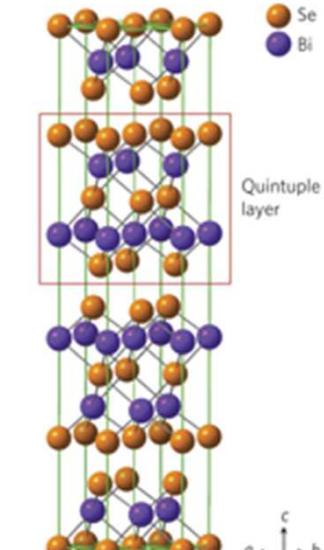
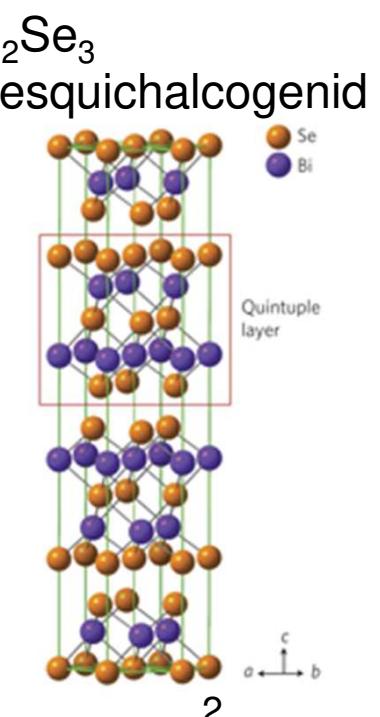
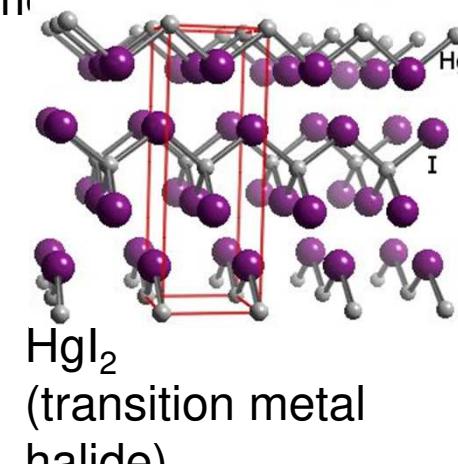
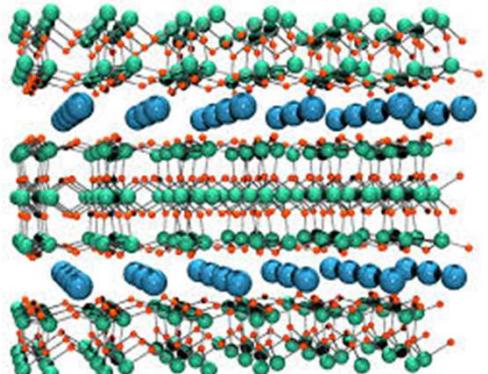
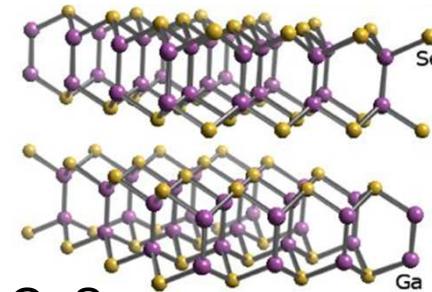
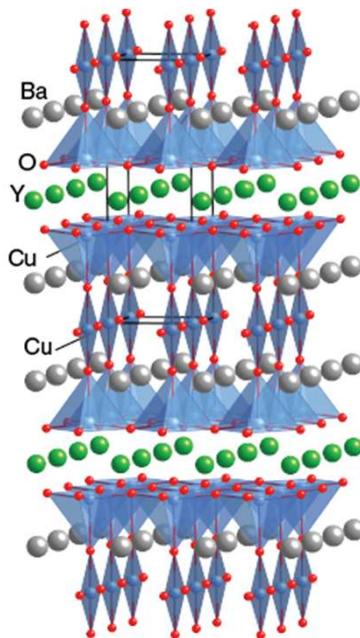
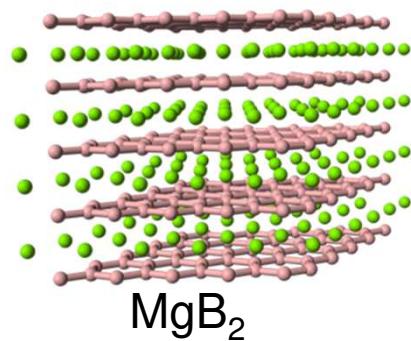
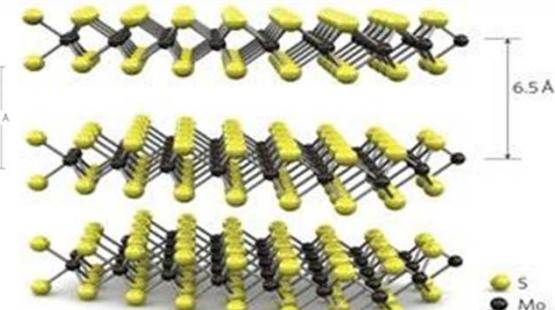
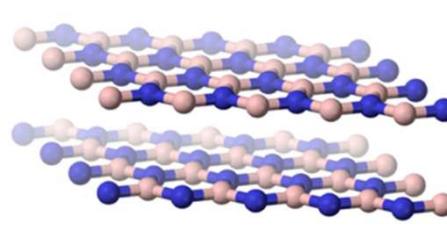
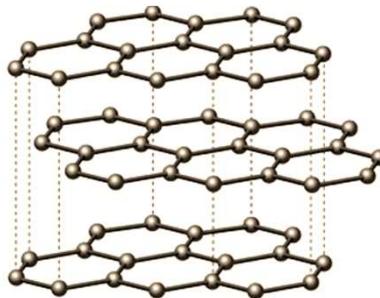
Electrical and Computer Engineering, Physics



231st ECS Meeting, 1 June 2017
New Orleans



layered materials



layered materials



C (graphite)



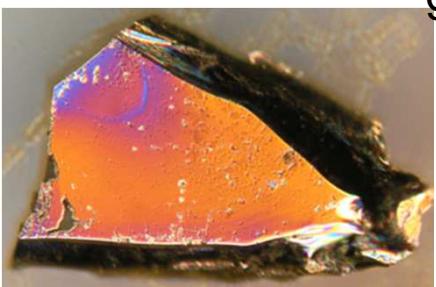
BN (white
graphite)



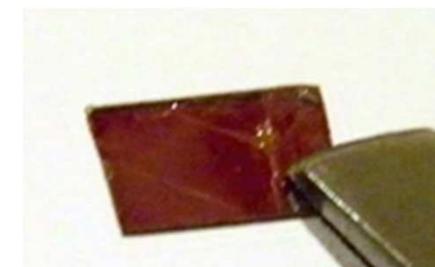
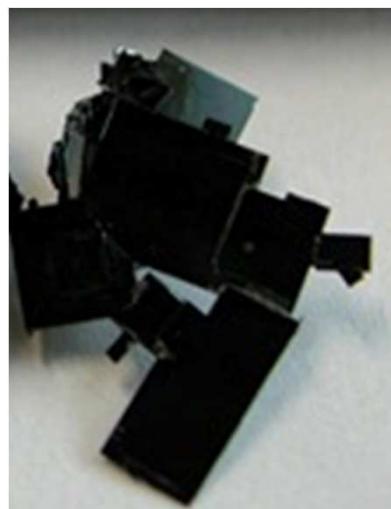
P (black-P)



MoS₂ (transition
metal dichalcogenide)



MgB₂



GaSe
(group III
monochalcogenide)



KAl₂(AlSi₃O₁₀)(OH)₂
(mica)

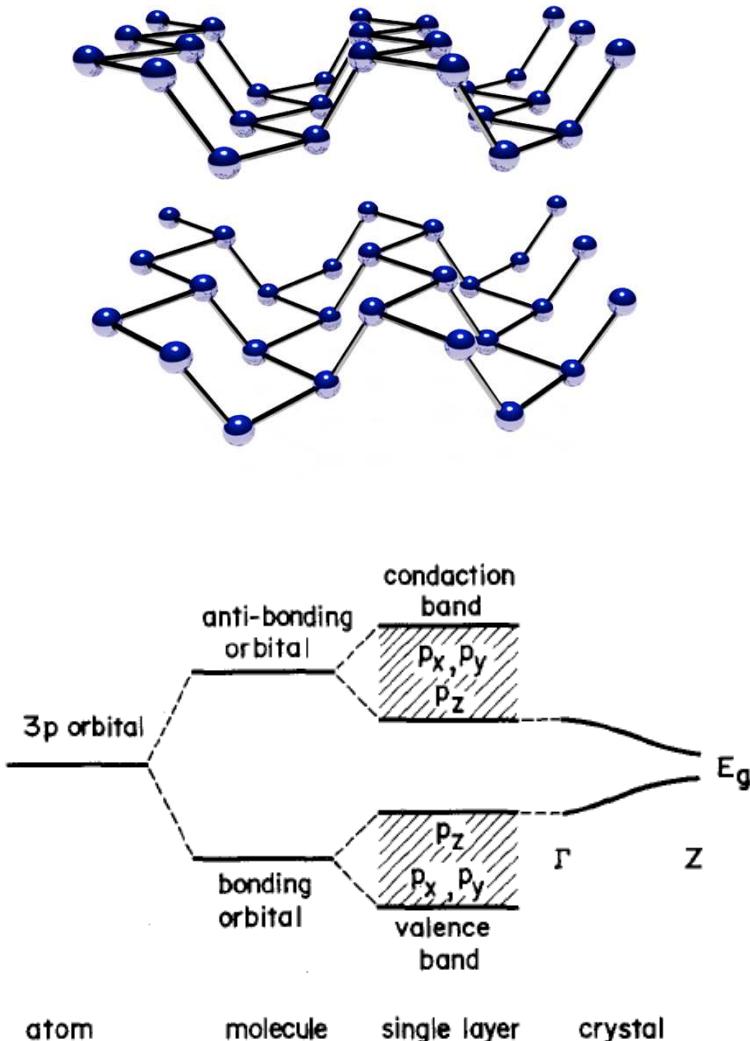
YBa₂Cu₃O_{7-x}
(high-T_c cuprate)



HgI₂
(transition metal
halide)



black phosphorus (bP)



1914: Bridgman produces first bP

1953: Keyes studies bP as a semiconductor

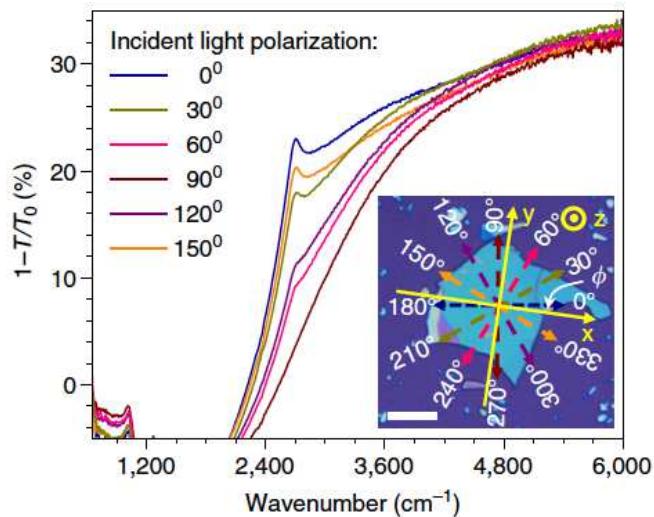
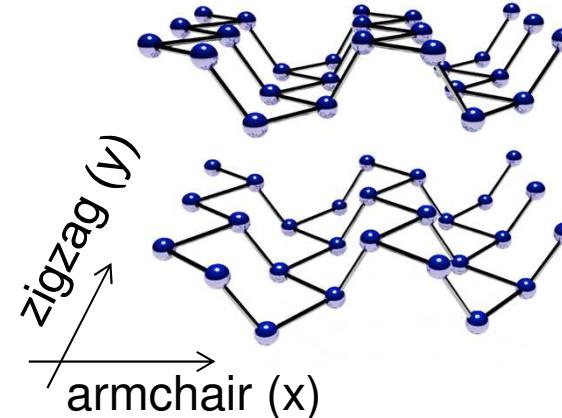
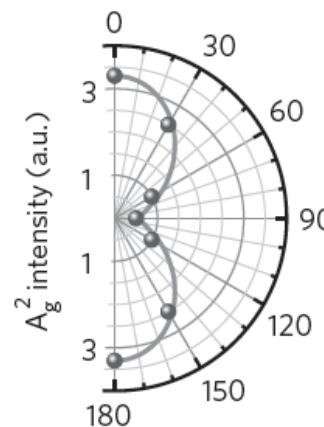
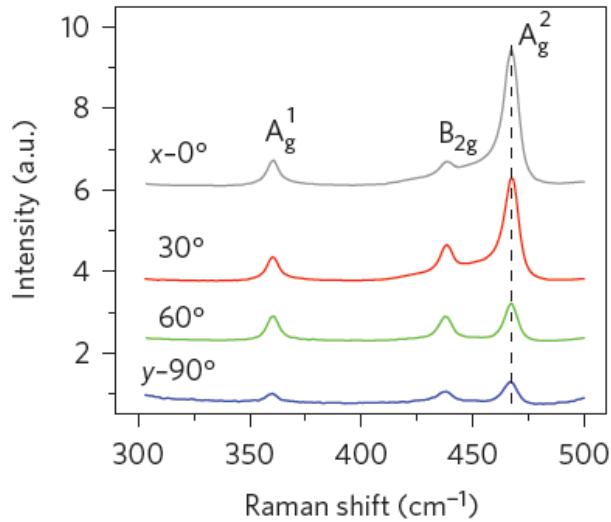
1968: Berman & Brandt; Witting & Mattias observe superconductivity at high pressure

1970's - 1980's: burst of activity in Japan on electronic properties, Raman, cyclotron resonance

2014: ultra-thin bP FETs reported by Yuanbo Zhang (Fudan) and Peide Ye (Purdue)
band gap = 0.3 eV

monolayer band gap \approx 1.2 eV

bP anisotropy



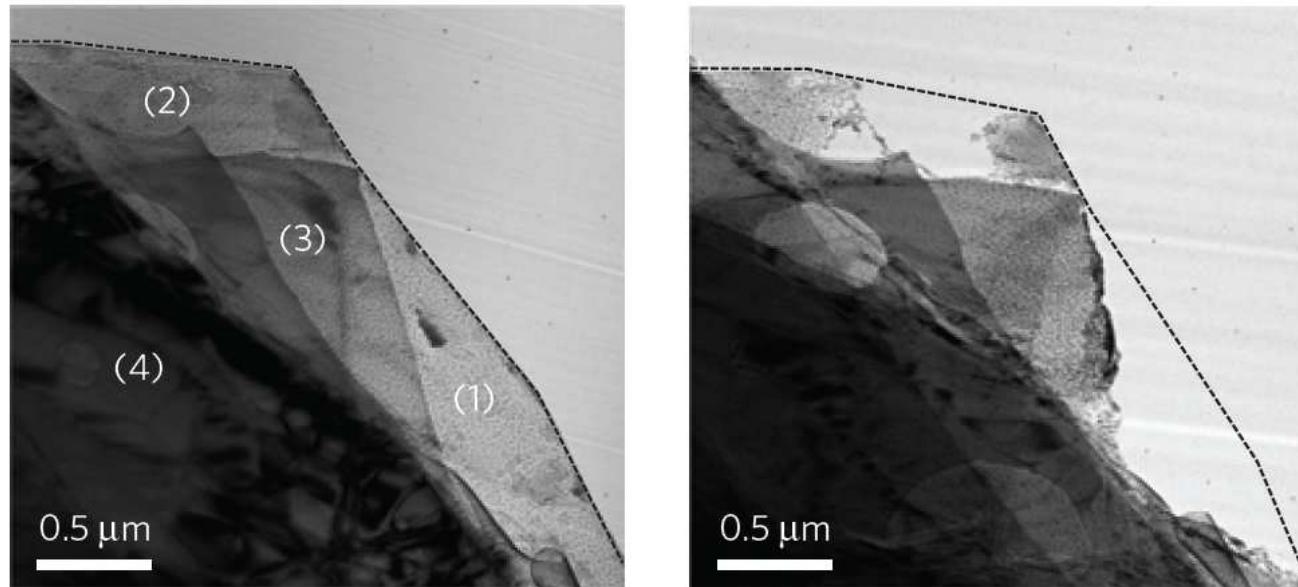
cyclotron effective mass

	m_x	m_y	m_z
electron	0.083	1.027	0.128
hole	0.076	0.648	0.280

S. Narita, et al. J. Phys. Soc. Jpn.
52, 3544 (1983)

Fengnian Xia..., Nature Comm.
2014, Nature Comm. 2015.

bP photo-oxidation



20s exposure to ambient air + light

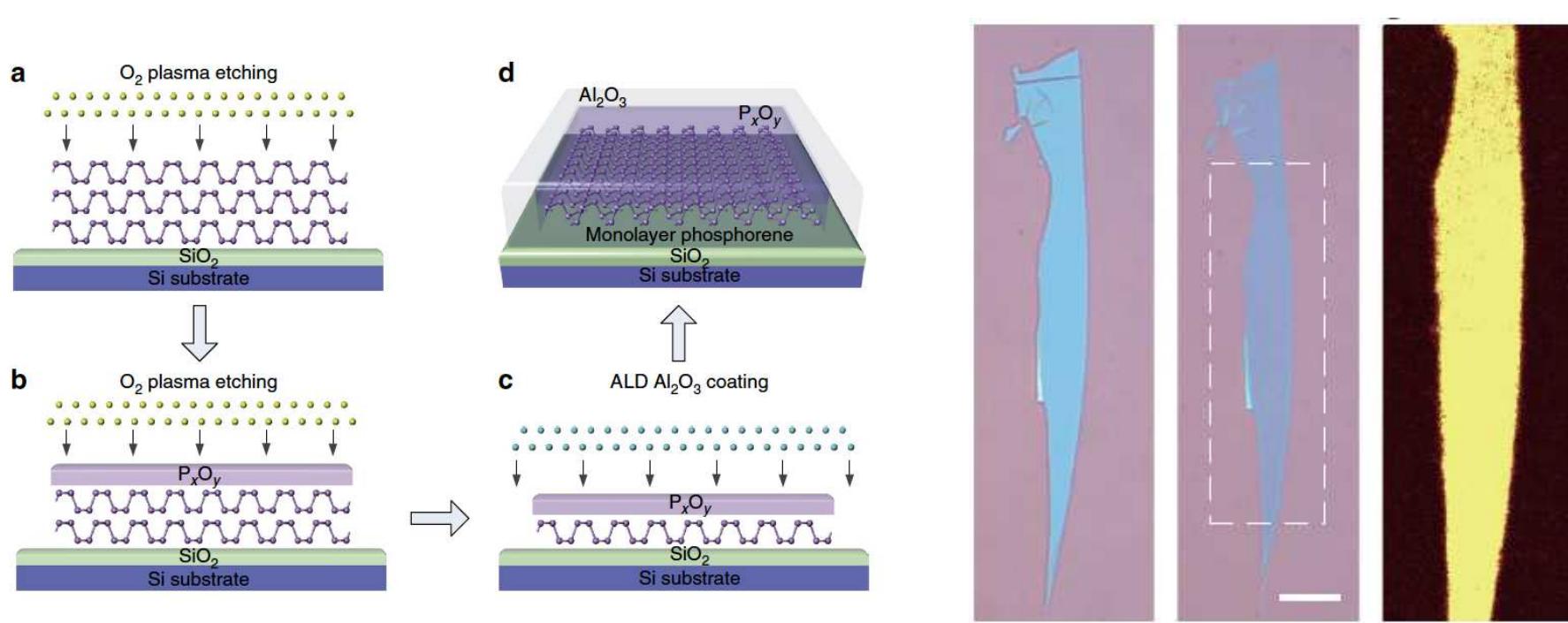
Rapid bP photo-oxidation with combination of O_2 , H_2O and light

outline

- oxidation for top-gated field effect transistors
- weak-localization & magnetoresistance and anisotropy

manuscript in preparation

oxidation for passivation and thinning

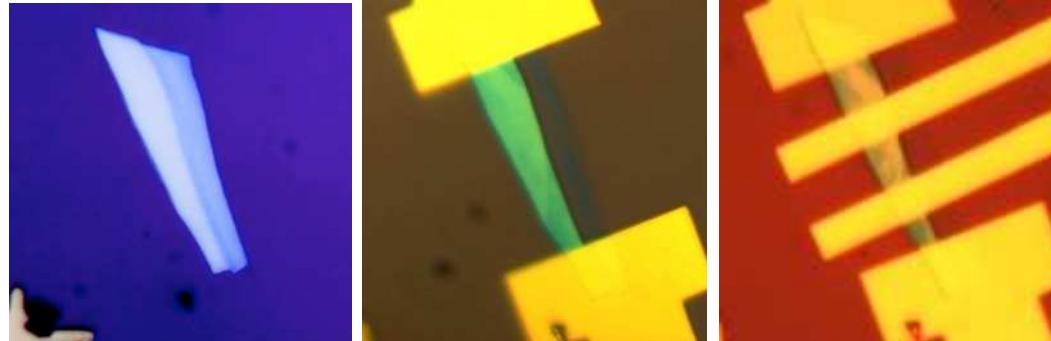


oxidation
formation
PL efficiency is preserved. Can oxidation be
used for gate dielectrics?

PL

microscop
y

bP FET fabrication

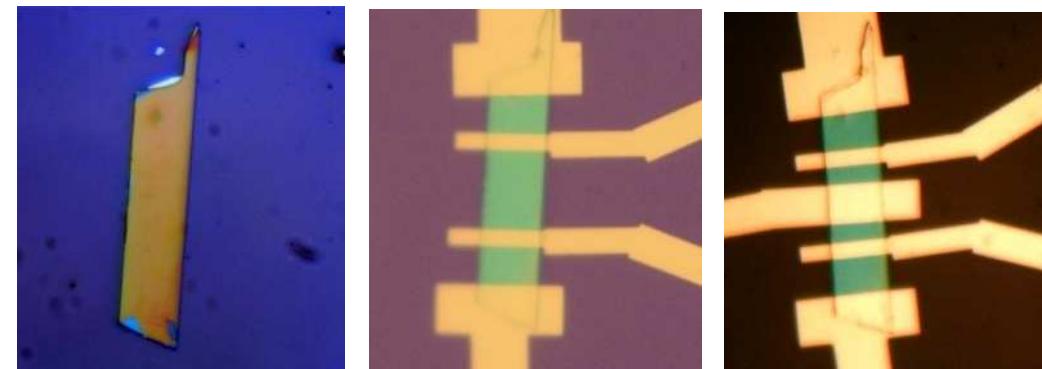


bulk bP source:
>99.9% purity



exfoliation & processing in glove box

O₂, H₂O < 1 ppm

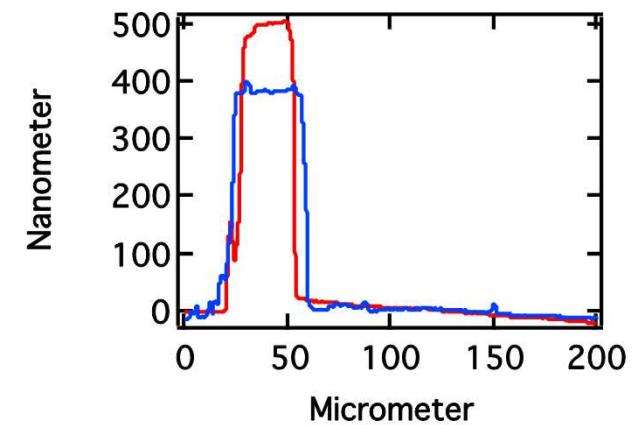
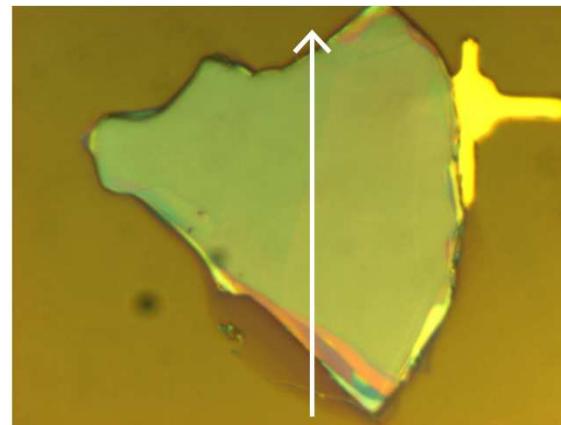
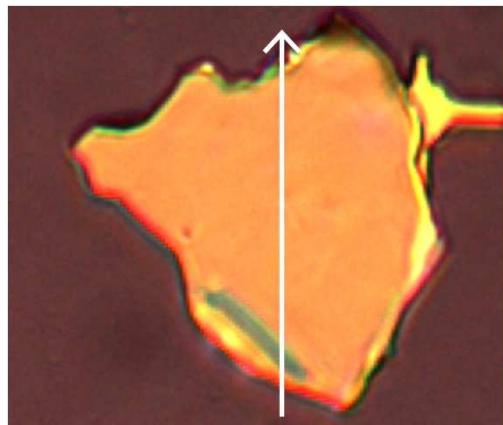


e-beam lithography, Ti/Au contacts

oxidation: 200 mTorr, 300 W RF,
1-3 minutes

e-beam lithography, Ti/Au top gates

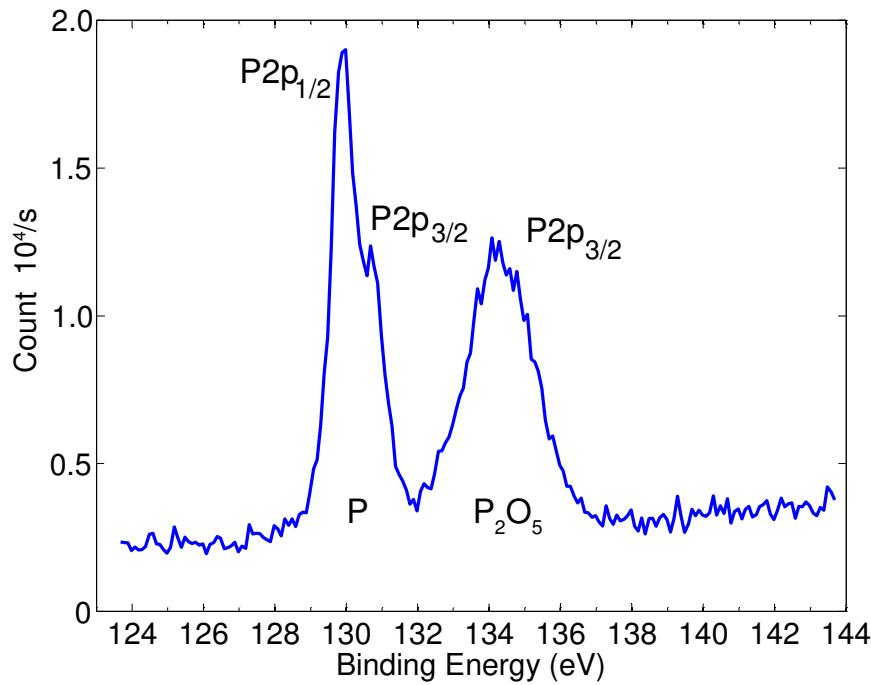
etch rate by oxidation



oxidation: 10sccm O₂, 200 mTorr, 300 W RF

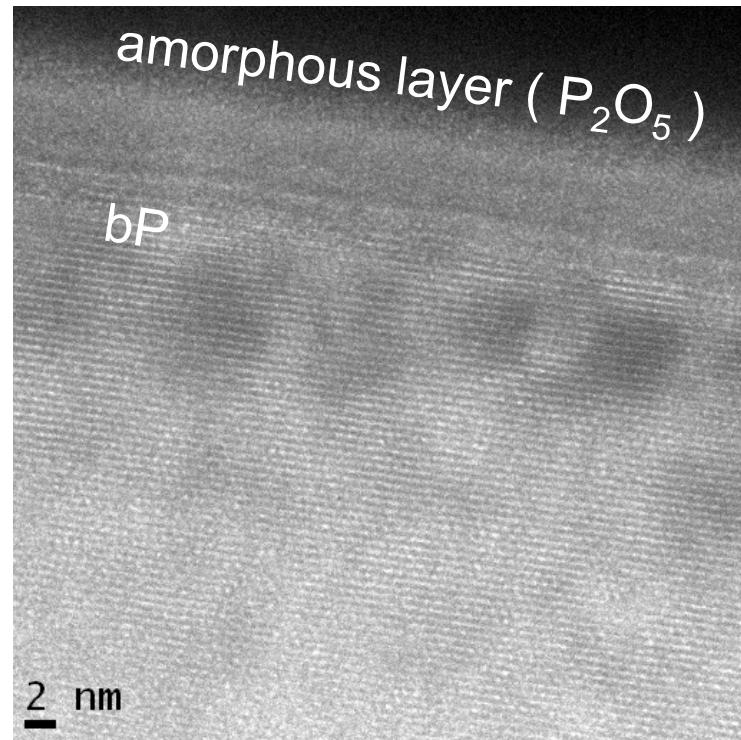
etch rate: 0.10 nm/s or ~0.5 bP layers/s

XPS + TEM



oxidation of bulk bP crystal

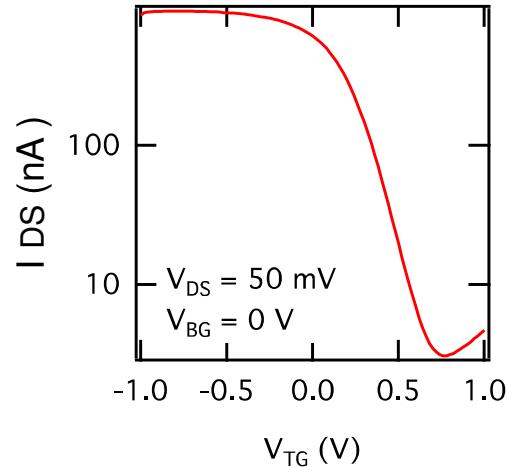
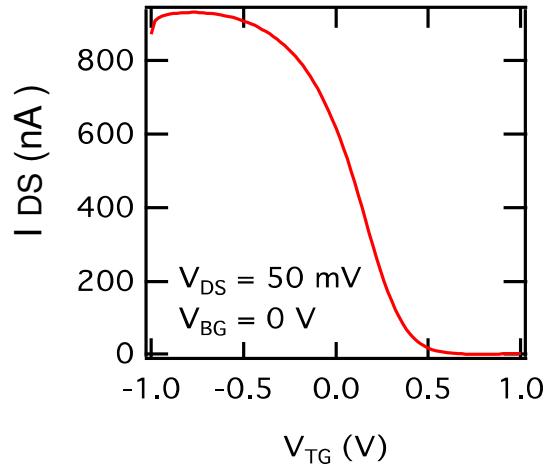
XPS: elemental P and P₂O₅ present



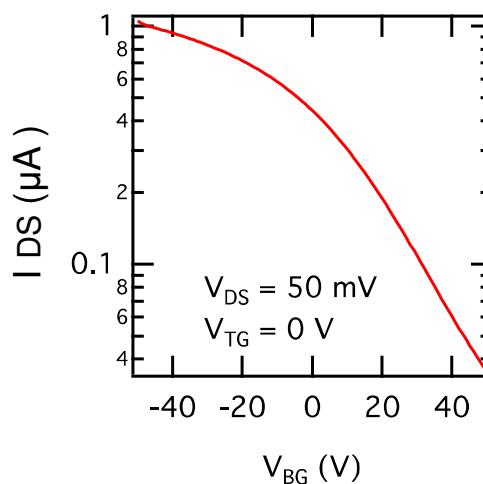
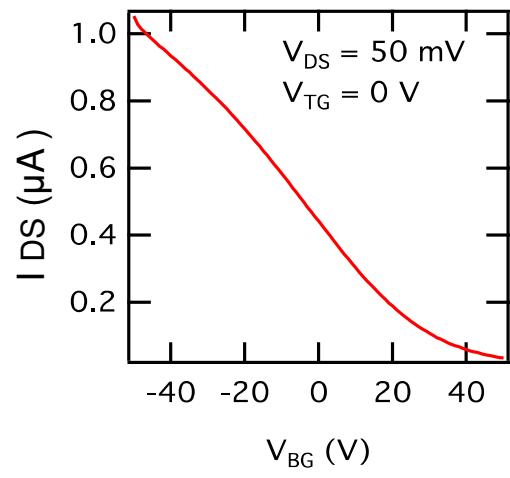
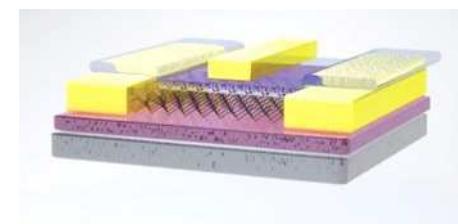
oxidation of bP flake on SiO₂/Si

TEM: amorphous layer (< 6nm thick), interfacial roughness with bP

field effect

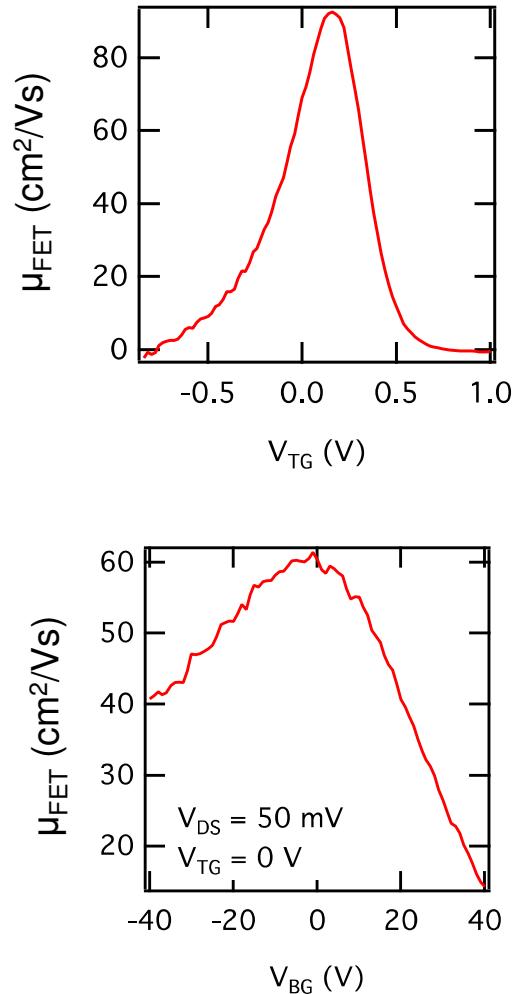
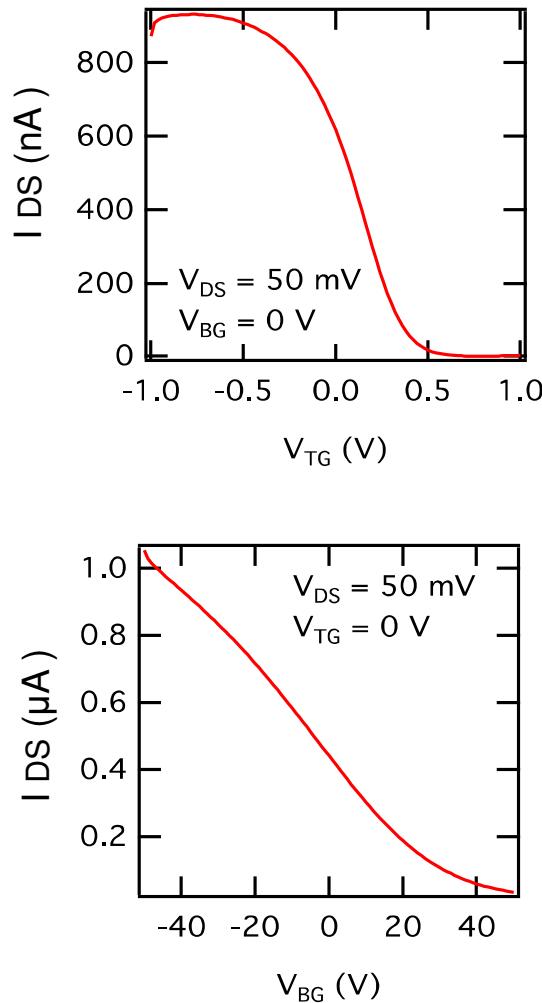


top gate modulation



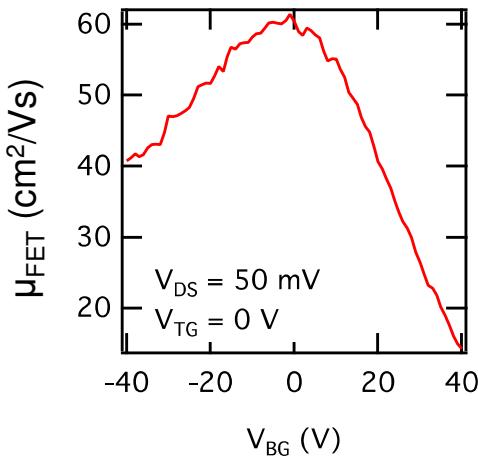
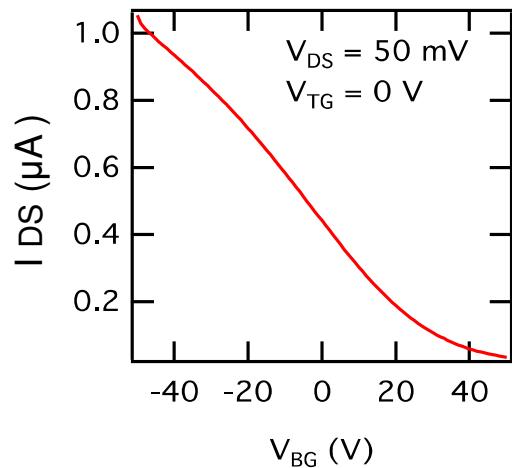
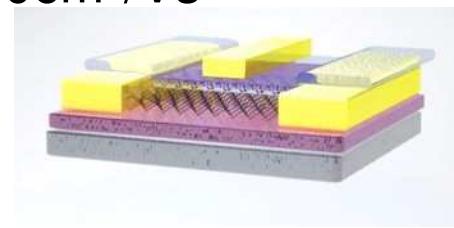
bottom gate modulation

field effect mobility



top gate modulation

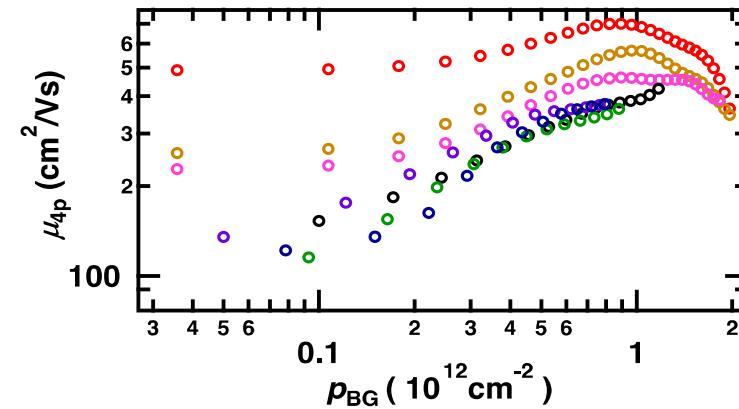
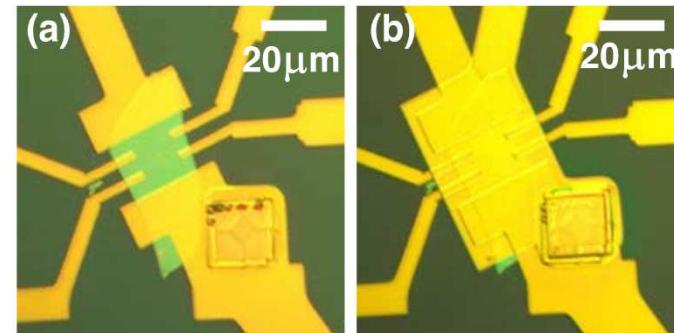
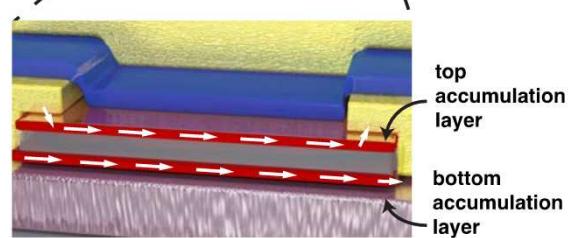
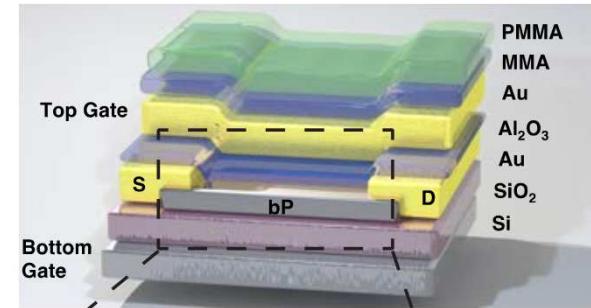
peak FET mobility:
90cm²/Vs



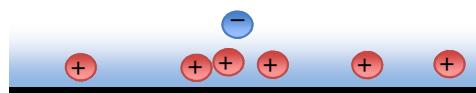
bottom gate modulation

peak FET mobility:
60cm²/Vs

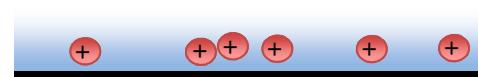
mobility limiting mechanisms



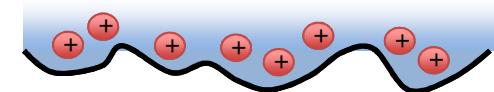
(c)



impurities



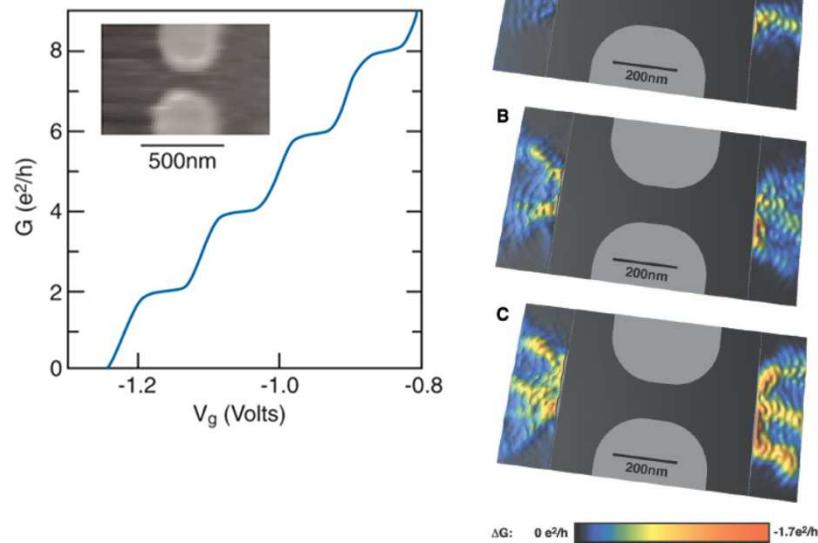
remote impurities



surface roughness
scattering

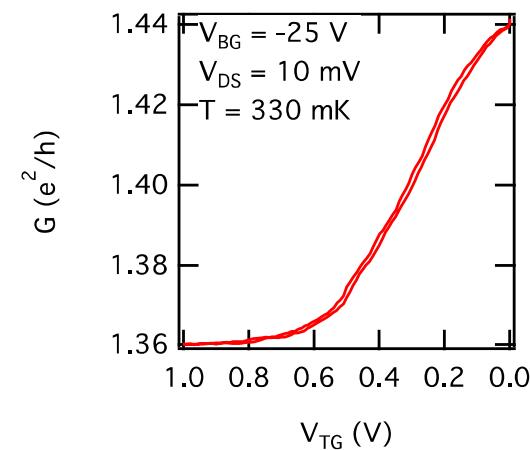
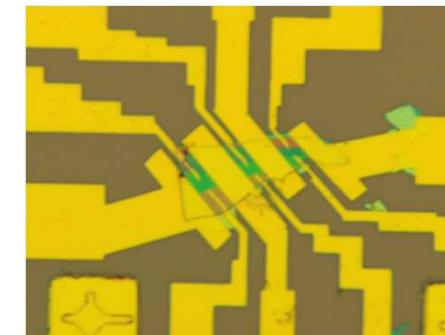
future: split gate transistors

GaAs/AlGaAs quantum point contacts



M.A. Topinka, et al., Science **289**, 2323 (2000).

bP split-gate structures

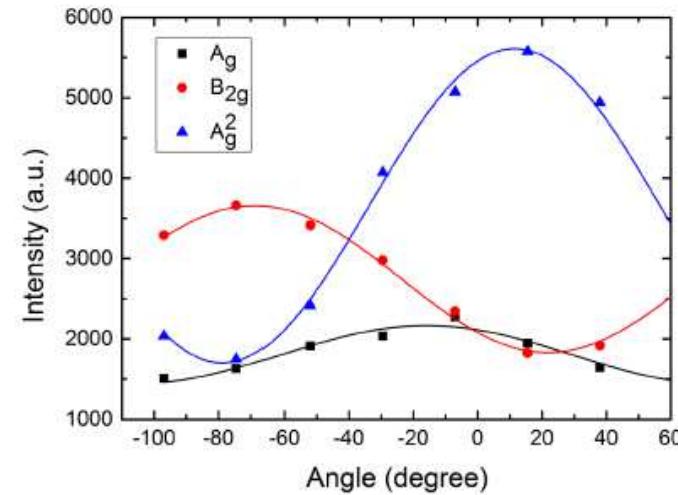
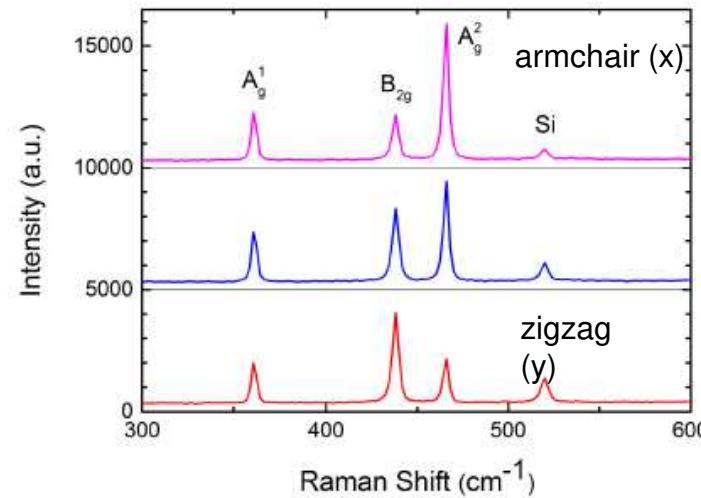
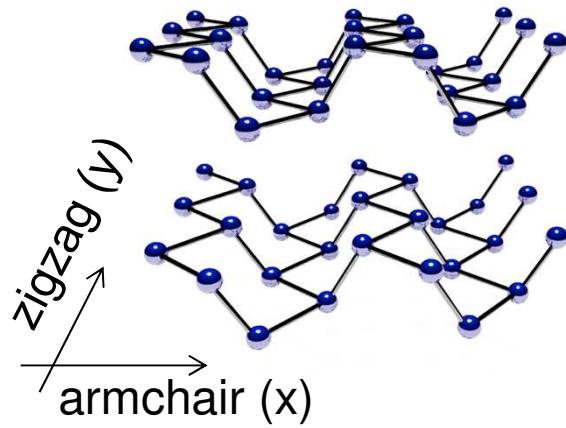
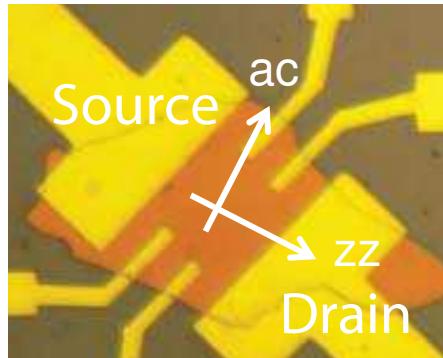


outline

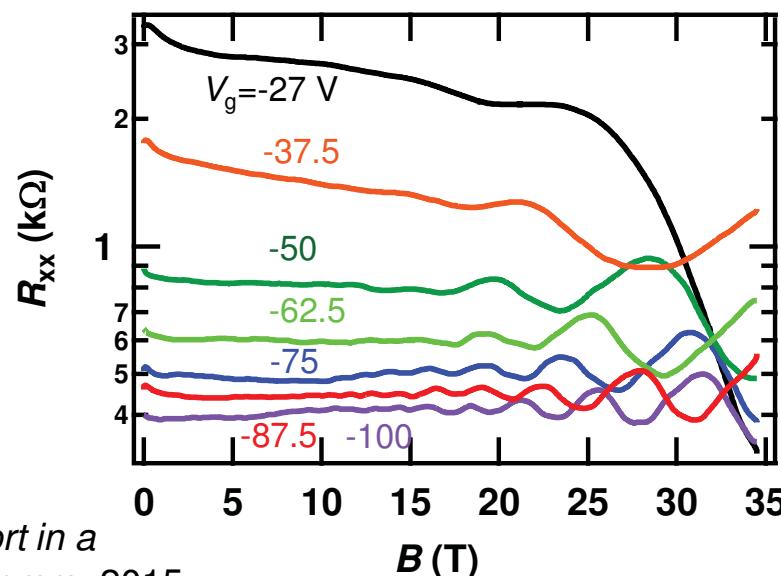
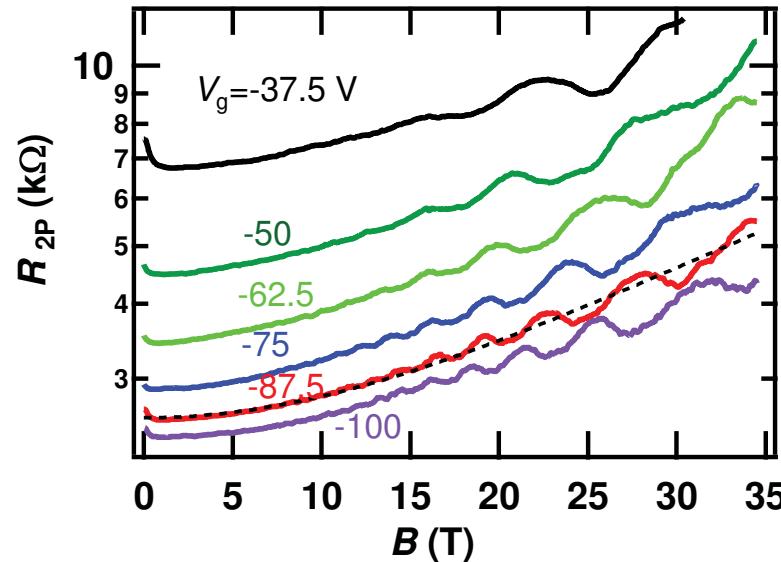
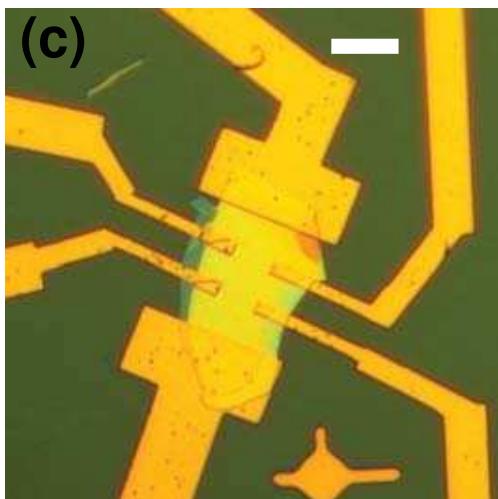
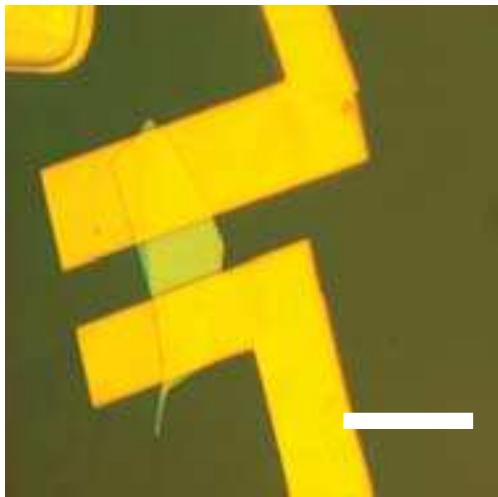
- oxidation for top-gated field effect transistors
- weak-localization & magnetoresistance and anisotropy

*N. Hemsworth, V. Tayari, F. Telesio, S. Xiang, S. Roddaro, M. Caporali, A. Ienco, M. Serrano-Ruiz, M. Peruzzini, G. Gervais, T. Szkopek, and S. Heun, Dephasing in strongly anisotropic black phosphorus, Phys. Rev. B **94**, 245404 (2016).*

anisotropy : Raman spectroscopy

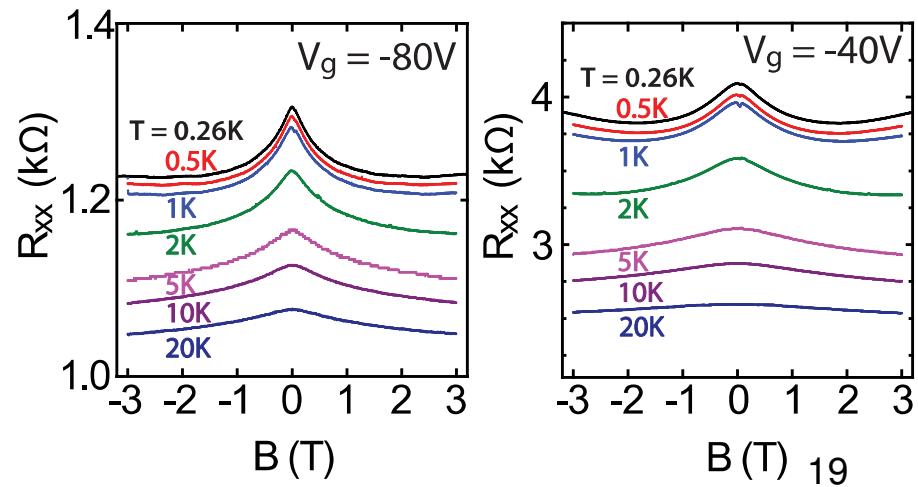
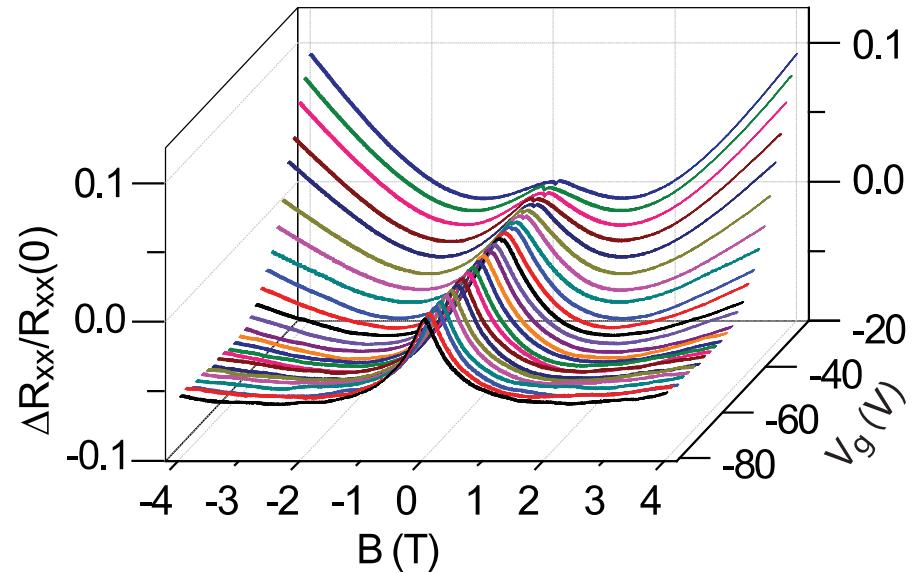
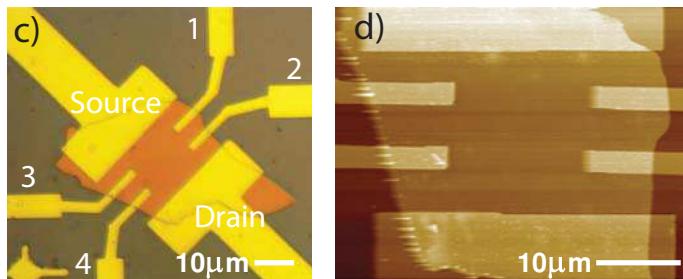
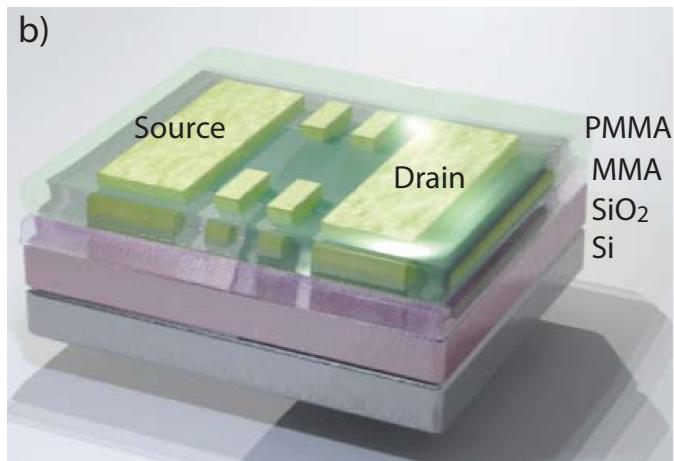


magnetoresistance



V. Tayari et al., *Two dimensional magnetotransport in a naked black phosphorus quantum well*, Nature Comm. 2015.

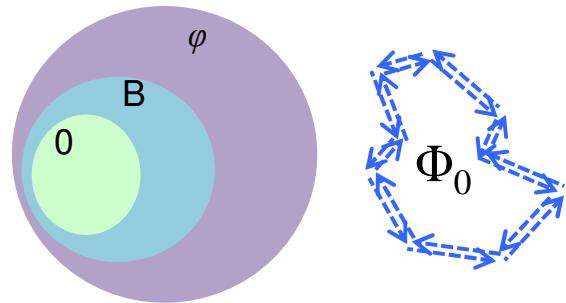
weak localization



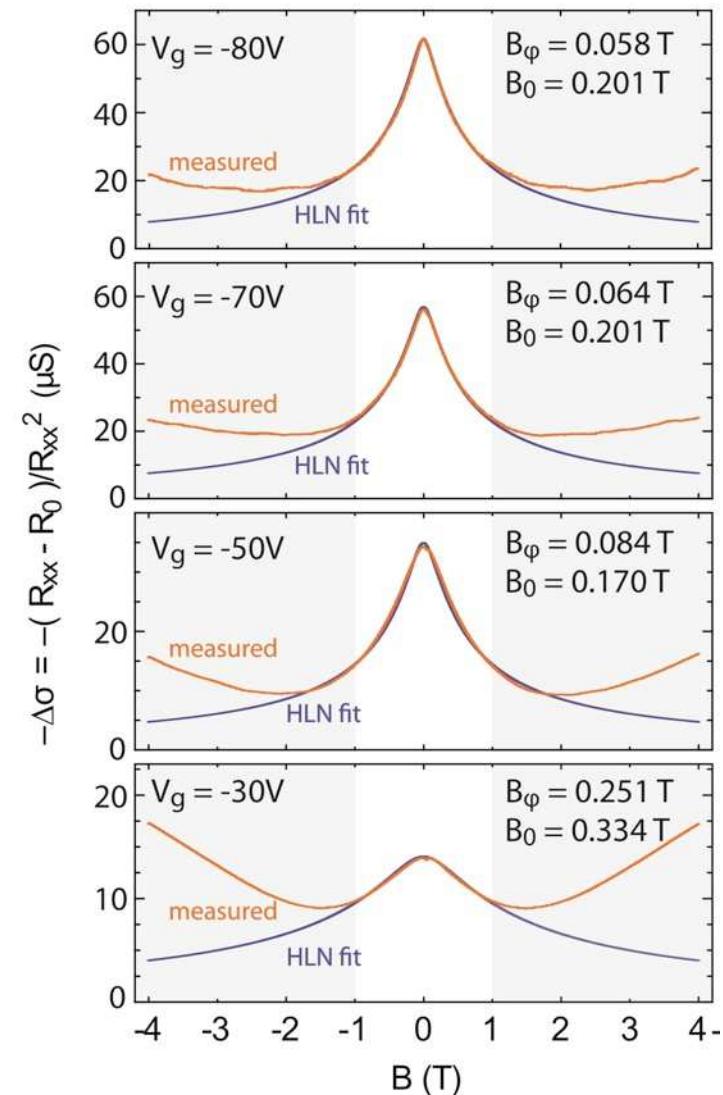
weak localization – fit with theory

$$\Delta\sigma(B) = -\frac{e^2}{2\pi^2 h} \left[\Psi\left(\frac{1}{2} + \frac{B_0}{B}\right) - \Psi\left(\frac{1}{2} + \frac{B_\varphi}{B}\right) \right]$$

$\Psi(x)$ = digamma function

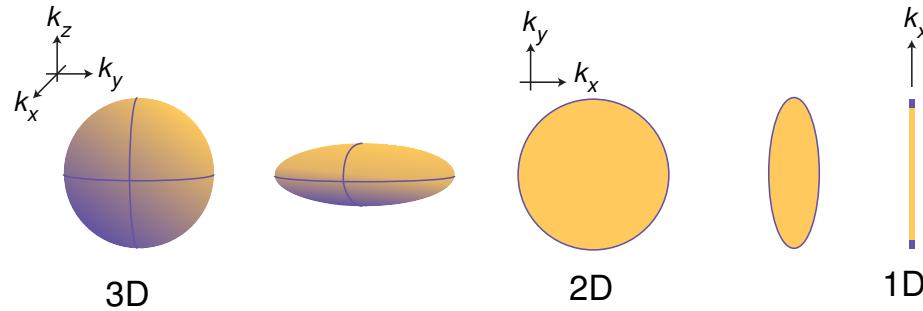
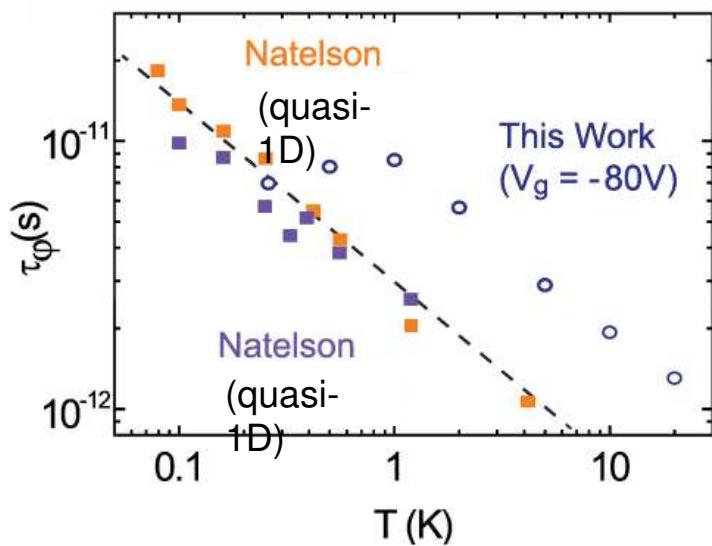
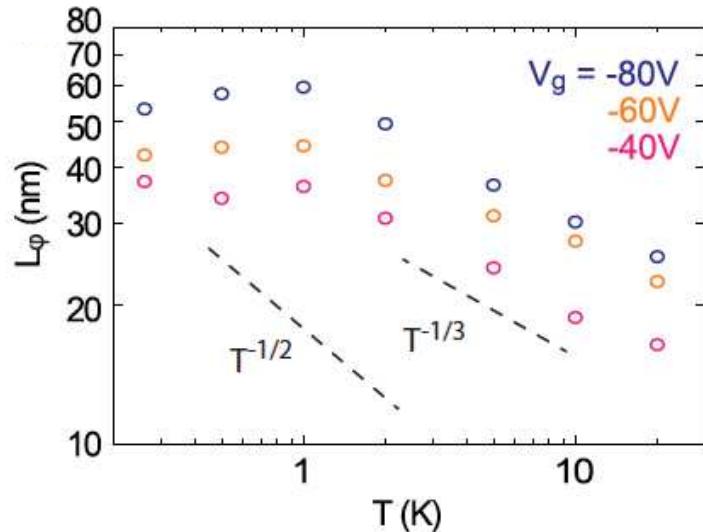


elastic scattering length: $\tau_0 = \sqrt{D\tau_0}$
inelastic scattering length: $\tau_\varphi = \sqrt{D\tau_\varphi}$



S. Hikami, A I. Larkin, and Y. Nagaoka,
 Prog. of Theor. Phys. **63**, 707 (1980).

localization & anisotropy



Electron-electron scattering in a diffusive 2D conductor:

$$\varphi \propto T^{-1/2}$$

$$\tau_\varphi = T^{-1}$$

Altshuler, Khmel'nitzkii, Larkin, Lee, PRB (1980).

Abrahams, Anderson, Lee, and Ramakrishnan, PRB (1981).

Electron-electron scattering in a diffusive 1D conductor:

$$\varphi \propto T^{-1/3}$$

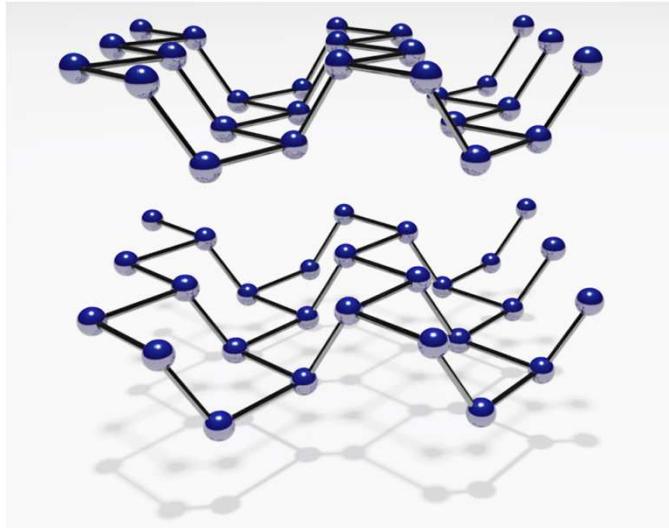
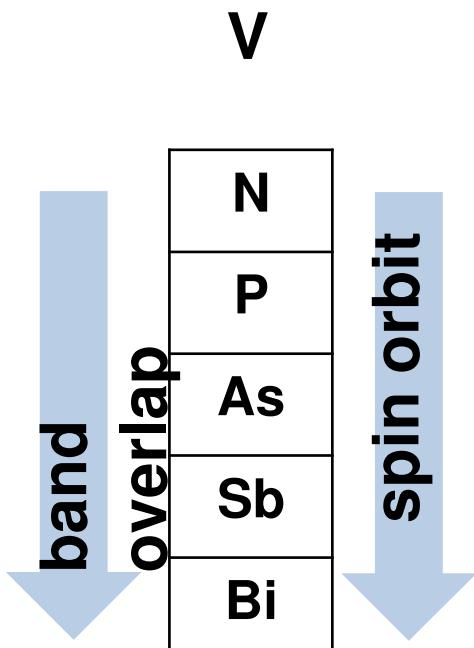
$$\tau_\varphi = T^{-2/3}$$

Appenzeller, Martel, Avouris, Stahl, Hunger, Lengeler, PRB (2001).

21

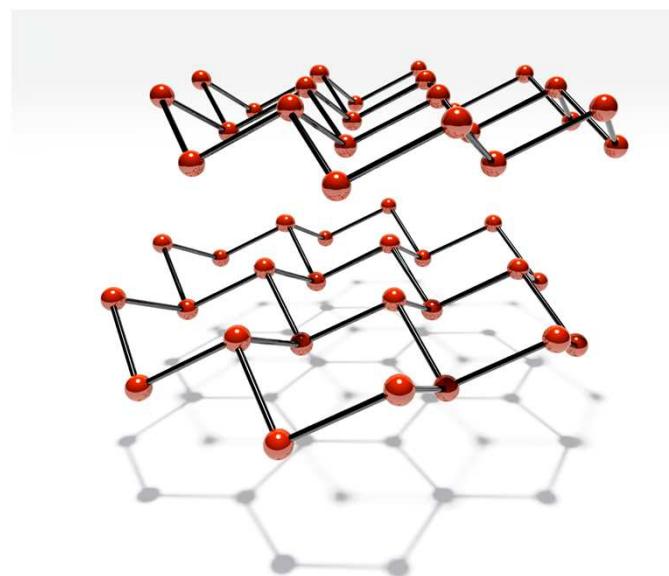
Natelson, Willett, West, and Pfeiffer, PRL (2001).

future: pnictogens



P :

puckered
honeycomb



As, Sb, Bi :

buckled
honeycomb

the team



Vahid
Tayari



Francesca
Telesio



Nick
Hemsworth



Will
Dickerson



Ibrahim
Fakih

Maurizio
Peruzzini
Firenze



Stefan
Heun
Pisa



Guillaume
Gervais
McGill



Tomasz
Szkopek
McGill



thank you